



TECHNICAL SPECIFICATION



**Nanomanufacturing – Key control characteristics –
Part 6-9: Graphene-based material – Sheet resistance: Eddy current method**

INTERNATIONAL
ELECTROTECHNICAL
COMMISSION

ICS 07.120

ISBN 978-2-8322-4306-0

Warning! Make sure that you obtained this publication from an authorized distributor.

CONTENTS

FOREWORD.....	4
INTRODUCTION.....	6
1 Scope.....	7
2 Normative references	7
3 Terms and definitions	7
3.1 General terms	8
3.2 Terms related to the measurement method	8
3.3 Key control characteristics	9
4 Abbreviated terms	10
5 General	10
5.1 Measurement principle	10
5.2 Measurement configuration	10
5.3 Measurement mode	11
5.3.1 Single point mode	11
5.3.2 Imaging scanning mode	11
5.4 Measurement system	11
5.4.1 Measurement equipment	11
5.4.2 Calibration standards.....	12
5.4.3 Ambient conditions	12
5.4.4 Sample preparation method.....	13
6 Measurement procedure	13
6.1 Calibration of test equipment	13
6.2 Verifying calibration	14
6.3 Description of the measurement procedure	14
7 Data analysis / interpretation of results	14
7.1 Single point sheet resistance measurement	14
7.2 Sheet resistance imaging.....	15
7.2.1 General	15
7.2.2 Line profile analysis.....	15
7.2.3 Histogram analysis	15
7.2.4 Statistical analysis.....	15
7.3 Individual homogeneity assessment.....	15
7.4 Defect identification	15
8 Test report.....	16
8.1 General.....	16
8.2 Sample identification.....	16
8.3 Test conditions	16
8.4 Measurement specific information.....	16
8.5 Test results.....	16
Annex A (informative) Worked example and test report.....	17
A.1 General.....	17
A.2 Sample identification.....	17
A.3 Geometry of the sample and scanning method.....	18
A.4 Measurement related information.....	18
Annex B (informative) Comparison between eddy current and four point probe measurement.....	20

B.1	General.....	20
B.2	Results	20
Annex C (informative)	Use case quality inspection	22
C.1	General.....	22
C.2	Analysis of the sheet resistance distribution for quality inspection.....	22
C.3	Analysis example	22
Annex D (informative)	Reference sample sets.....	25
Bibliography.....		26
Figure 1	– Scheme of measurement setup	12
Figure A.1	– Sheet resistance map with histogram.....	19
Figure B.1	– Correlation of the results of sheet resistance measured by the eddy current (EC) method and by the four point probe (4PP) method	21
Figure C.1	– Sheet resistance image of 200 mm × 200 mm graphene sheet.....	22
Figure C.2	– Line profile analysis	23
Figure C.3	– Histogram view of the whole sample	23
Figure C.4	– Histogram analysis (high sheet resistance area).....	23
Figure C.5	– Histogram analysis (good area)	24
Figure C.6	– Selective area analysis (used specified shape).....	24
Figure C.7	– Selective area analysis (regular shape)	24
Figure D.1	– Sheet resistance reference sample set 300 mm × 300 mm	25
Table A.1	– Product identification	17
Table A.2	– General material description	17
Table A.3	– Geometry of the sample and scanning parameter.....	18
Table A.4	– Measurement related information	18
Table A.5	– Test results: Sheet resistance	18
Table B.1	– Comparison of the results of sheet resistance measured by the eddy current method and by the four point probe method	20
Table B.2	– Measurement accuracy	21

INTERNATIONAL ELECTROTECHNICAL COMMISSION

NANOMANUFACTURING – KEY CONTROL CHARACTERISTICS –

Part 6-9: Graphene-based material – Sheet resistance: Eddy current method

FOREWORD

- 1) The International Electrotechnical Commission (IEC) is a worldwide organization for standardization comprising all national electrotechnical committees (IEC National Committees). The object of IEC is to promote international co-operation on all questions concerning standardization in the electrical and electronic fields. To this end and in addition to other activities, IEC publishes International Standards, Technical Specifications, Technical Reports, Publicly Available Specifications (PAS) and Guides (hereafter referred to as "IEC Publication(s)"). Their preparation is entrusted to technical committees; any IEC National Committee interested in the subject dealt with may participate in this preparatory work. International, governmental and non-governmental organizations liaising with the IEC also participate in this preparation. IEC collaborates closely with the International Organization for Standardization (ISO) in accordance with conditions determined by agreement between the two organizations.
- 2) The formal decisions or agreements of IEC on technical matters express, as nearly as possible, an international consensus of opinion on the relevant subjects since each technical committee has representation from all interested IEC National Committees.
- 3) IEC Publications have the form of recommendations for international use and are accepted by IEC National Committees in that sense. While all reasonable efforts are made to ensure that the technical content of IEC Publications is accurate, IEC cannot be held responsible for the way in which they are used or for any misinterpretation by any end user.
- 4) In order to promote international uniformity, IEC National Committees undertake to apply IEC Publications transparently to the maximum extent possible in their national and regional publications. Any divergence between any IEC Publication and the corresponding national or regional publication shall be clearly indicated in the latter.
- 5) IEC itself does not provide any attestation of conformity. Independent certification bodies provide conformity assessment services and, in some areas, access to IEC marks of conformity. IEC is not responsible for any services carried out by independent certification bodies.
- 6) All users should ensure that they have the latest edition of this publication.
- 7) No liability shall attach to IEC or its directors, employees, servants or agents including individual experts and members of its technical committees and IEC National Committees for any personal injury, property damage or other damage of any nature whatsoever, whether direct or indirect, or for costs (including legal fees) and expenses arising out of the publication, use of, or reliance upon, this IEC Publication or any other IEC Publications.
- 8) Attention is drawn to the Normative references cited in this publication. Use of the referenced publications is indispensable for the correct application of this publication.
- 9) Attention is drawn to the possibility that some of the elements of this IEC Publication may be the subject of patent rights. IEC shall not be held responsible for identifying any or all such patent rights.

IEC TS 62607-6-9 has been prepared by IEC technical committee 113: Nanotechnology for electrotechnical products and systems. It is a Technical Specification.

The text of this Technical Specification is based on the following documents:

Draft	Report on voting
113/569/DTS	113/625/RVDTS

Full information on the voting for its approval can be found in the report on voting indicated in the above table.

The language used for the development of this Technical Specification is English.

This document was drafted in accordance with ISO/IEC Directives, Part 2, and developed in accordance with ISO/IEC Directives, Part 1 and ISO/IEC Directives, IEC Supplement, available

at www.iec.ch/members_experts/refdocs. The main document types developed by IEC are described in greater detail at www.iec.ch/standardsdev/publications.

A list of all parts in the IEC TS 62607 series, published under the general title *Nanomanufacturing – Key control characteristics*, can be found on the IEC website.

The committee has decided that the contents of this document will remain unchanged until the stability date indicated on the IEC website under webstore.iec.ch in the data related to the specific document. At this date, the document will be

- reconfirmed,
- withdrawn,
- replaced by a revised edition, or
- amended.

IMPORTANT – The "colour inside" logo on the cover page of this document indicates that it contains colours which are considered to be useful for the correct understanding of its contents. Users should therefore print this document using a colour printer.

INTRODUCTION

The application of graphene and graphene-related materials as a conductive large-area electrode material has become of rising interest during recent years. Especially in the application of graphene as a replacement material for indium tin oxide (ITO), graphene combines low sheet resistance and high optical transparency. In particular, the application of optically transparent large-area graphene layers has become more important. Hence, the electrical characterization of large-area graphene layers is essential.

However, contacting methods, such as four-probe measurements, can cause damage to the graphene and deteriorate its quality.

Non-contact methods have advantages for measurement of the sheet resistance since damage to the layers is avoided and it is possible to readily scan the film to examine homogeneity.

The sheet resistance can serve as a measure for the electrical characterization due to its direct dependence on conductivity and graphene quality for electrical applications.

NANOMANUFACTURING – KEY CONTROL CHARACTERISTICS –

Part 6-9: Graphene-based material – Sheet resistance: Eddy current method

1 Scope

This part of IEC 62607 establishes a standardized method to determine the key control characteristic

- sheet resistance

for films of graphene-based materials by

- eddy current method.

With this method a coil-generated primary alternating electromagnetic field induces eddy currents in the conducting layer to be measured. The superposition of the primary field with the secondary field induced by the eddy currents is a function of the sheet resistance of the layer.

- The method is applicable for the contactless measurement of the sheet resistance of large area graphene layers on non-conductive substrates. As the method avoids any physical contact, it prevents any mechanical damage to the sensitive graphene layer. Therefore, the method is suitable for electrical characterization and quality control in an industrial fabrication environment.
- Due to the use of two detectors – one above the substrate and one below the substrate – the method is insensitive regarding small deviations from perfect flatness of the substrate.
- The range of graphene layers to be characterized comprises any quality, size and morphology of graphene crystallites. Hence, the applicability of this method spans from high quality, defect-free graphene layers to layers of dried graphene ink.
- The size of the graphene layers to be characterized includes layers larger than 25 mm × 25 mm for single point testing and 50 mm × 50 mm for imaging testing.
- The method can be used for layers of graphene-based material with a sheet resistance in the nominal range of 10 Ω/sq to 5 000 Ω/sq.

2 Normative references

There are no normative references in this document.